

Silicon Dioxide

Photoresist Aluminum

22 Deposition of Mask Oxide

FIG.7A

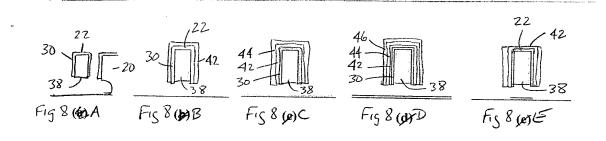
Resist Spin and Exposure
24 Resist Spin and Exposure
25 Anisotropic Oxide Etch
20 Pattern Transfer
24 FIG.7C

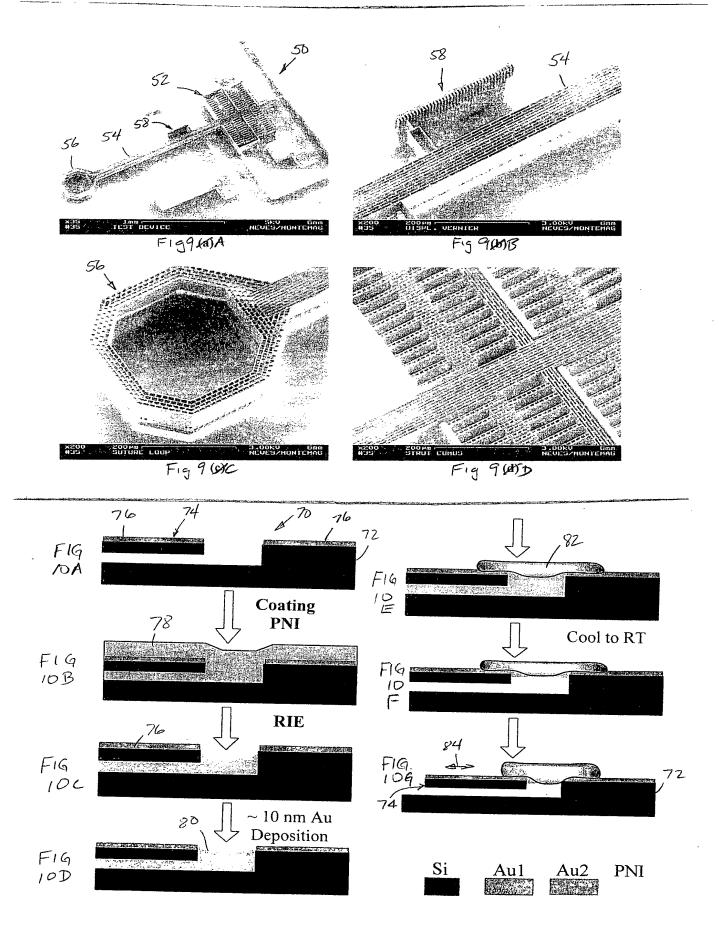
Silicon Dioxide

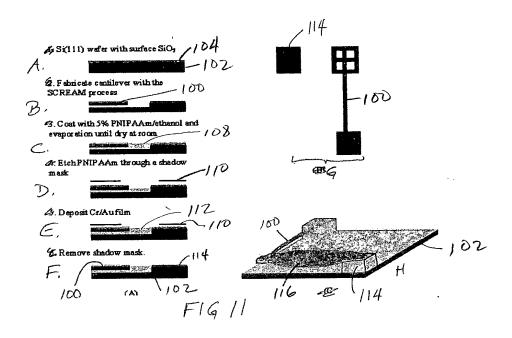
Conformal Deposition of 30 Isotropic Release Etch

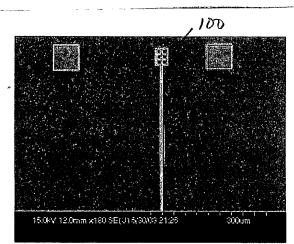
7 I 38

Anisotropic Oxide Etch
22 Silicon Etch
23 Anisotropic Oxide Etch
24 Sputtering
40 Al 40 Sputtering
40 Sputtering
40 Al 50 Sputtering
40 Al 40 Al 40 Sputtering
40 Al 40 Al









15.0% 12.0max x10 SE (U) 5:30,003 21:18

106

F1612 (A)

F1G 12(B)

م الربه

